

IN THE ABSTRACT:

Please amend the abstract as shown below.

ABSTRACT

~~Provided is a~~ A developing apparatus which enables the time necessary for a development reaction to be shortened and permits uniform development.—~~A includes a~~ includes a chuck device 2 ~~comprises with~~ with a support portion 21 whose top surface is a horizontal surface and a spinner 22 disposed in the middle of this support portion 21. The support portion and the spinner are provided within an antiscattering cup 23. A groove which vacuum adsorbs a substrate W to be treated is formed on the top surface of the ~~above-described~~ spinner 22, a pipe which forms a circulation path 9 is disposed within the groove formed on the top surface of the support portion 21, and a cleaning nozzle 24 which cleans a developing solution which has flown behind the rear surface of the substrate W ~~to be treated~~ is disposed in a position which is nearest to the inside diameter of the top surface of the support portion 21. On the other hand, in a nozzle device 3, a spray nozzle 33 is attached to a horizontally reciprocating arm 31 via a columnar support 32. A developing solution pipe and an air supply pipe are inserted into this spray nozzle 33 and a temperature-regulated developing solution from the developing solution supply pipe is spouted in mist form from the bottom end of the spray nozzle 33.